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(12) **United States Design Patent**
Ota

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(54) **COVER FOR A HEATER STAGE OF A PLASMA PROCESSING APPARATUS**

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(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(52) **U.S. Cl.** **D15/138**; D15/199

(58) **Field of Classification Search** D7/586,
D7/587; D8/70, 74; D9/445, 454; D15/133,
D15/144.1, 199; 117/103; 118/723 AN,
118/723 ME; 216/69; 257/E21.252; 427/562,
427/571, 575

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a cover for a heater stage of a plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front view of a cover for a heater stage of a plasma processing apparatus showing my new design:

FIG. 2 is a rear view thereof;

FIG. 3 is a right side view thereof;

FIG. 4 is a top plan view thereof;

FIG. 5 is a sectional view taken along line 5—5 of FIG. 1 thereof;

FIG. 6 is an enlarged view taken along line 6—6 of FIG. 5 thereof; and,

FIG. 7 is a perspective view thereof.

1 Claim, 3 Drawing Sheets

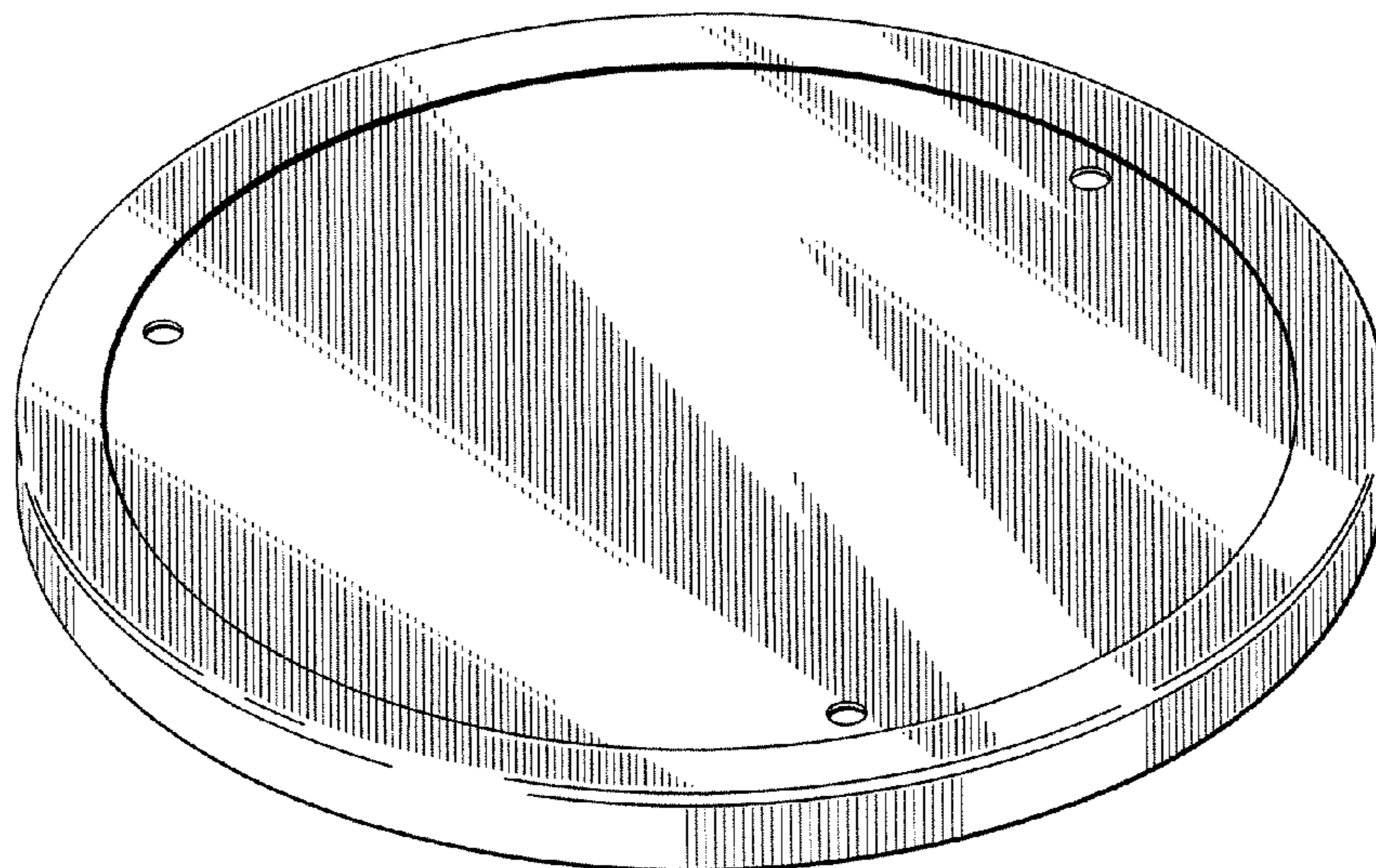


FIG.1

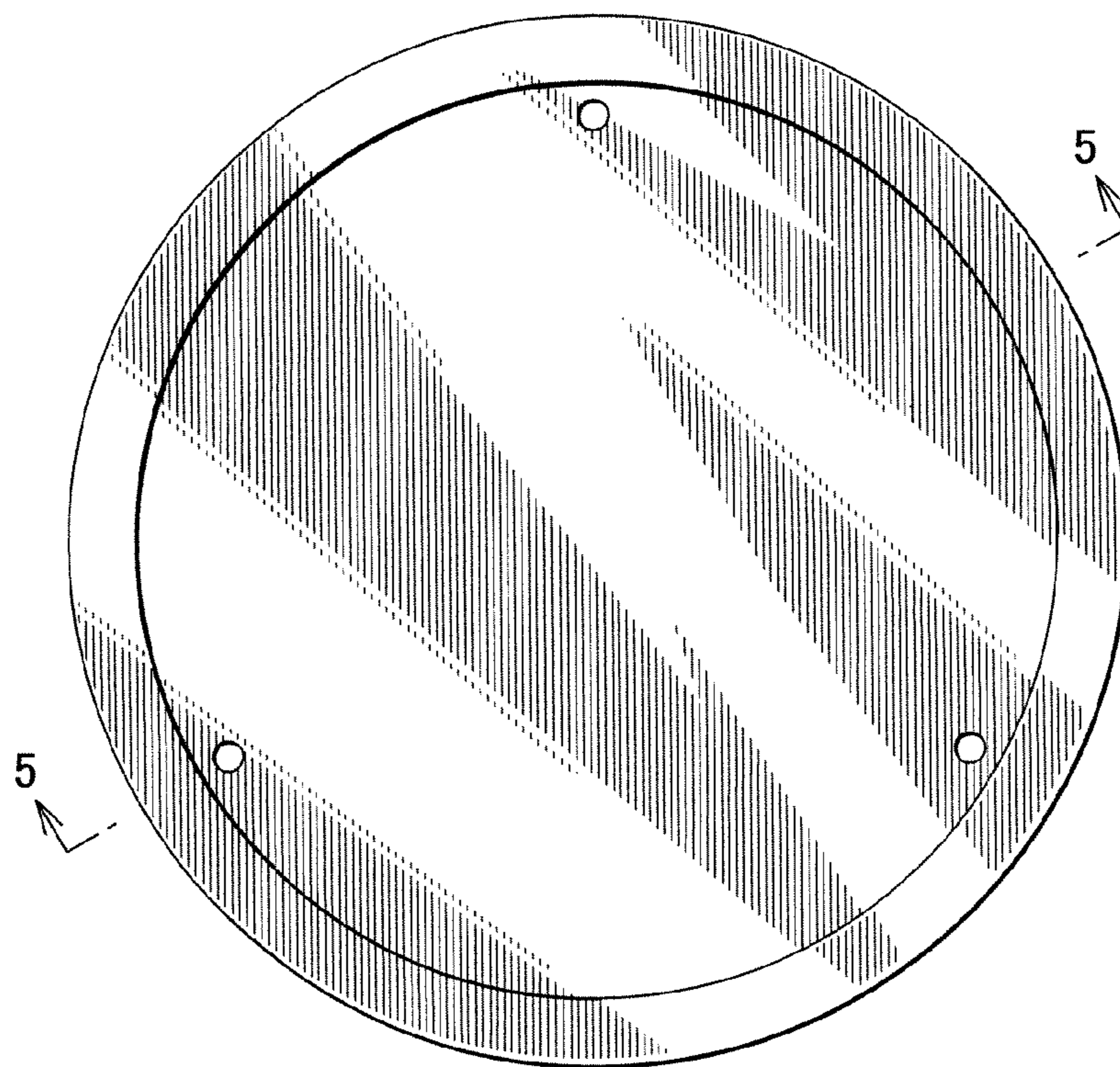


FIG.2

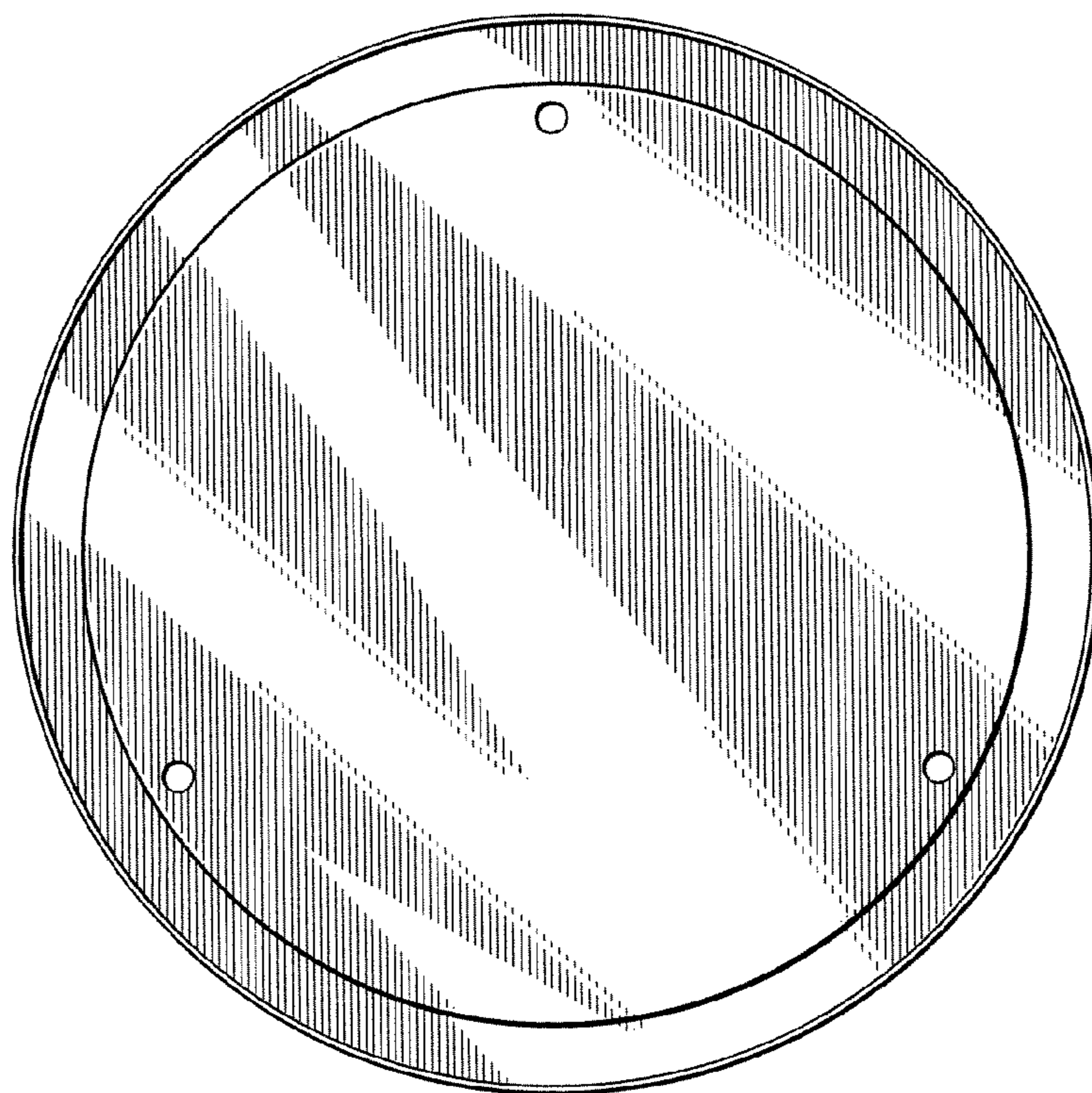


FIG.3



FIG.4



FIG.5

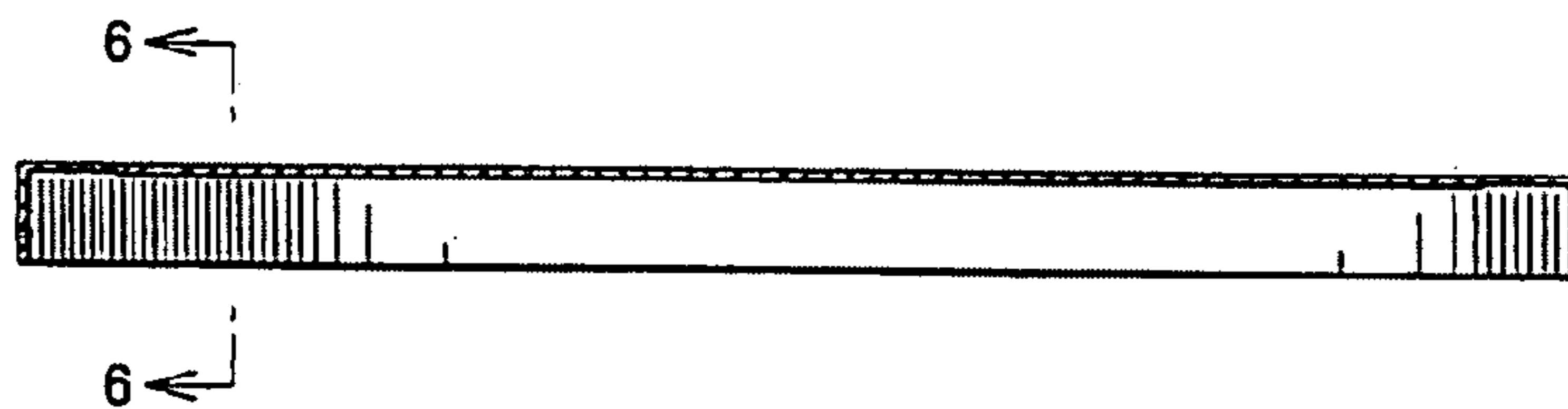


FIG.6

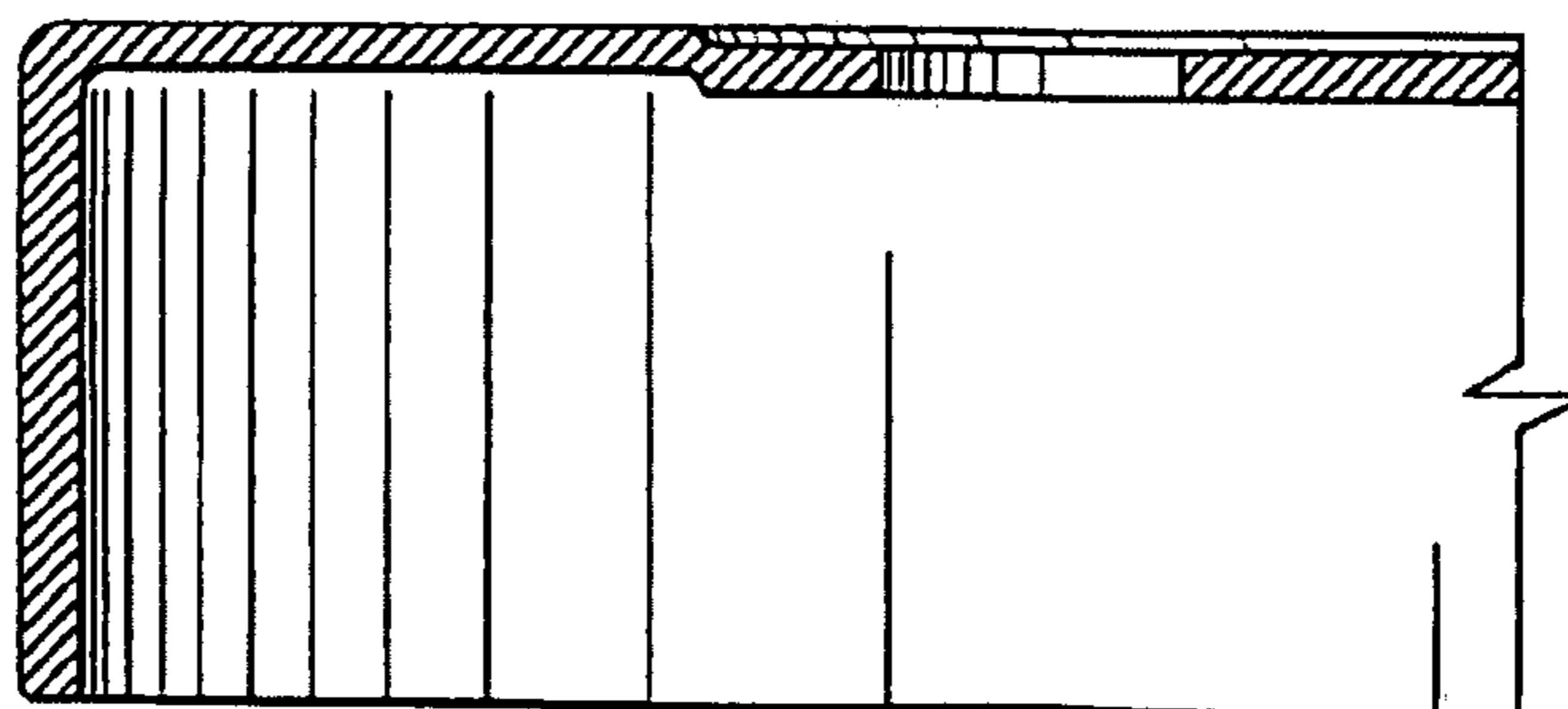


FIG. 7

